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		<i>DB=USPT; PLUR=YES; OP=ADJ</i>	
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<input type="checkbox"/>	L4	L3 and slawly	0
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<input type="checkbox"/>	L2	wafer and cleaning and removing	10782
<input type="checkbox"/>	L1	wafer and cleaning and slowly	2057

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☐ 11. Document ID: US 6070284 A

L5: Entry 11 of 18

File: USPT

Jun 6, 2000

US-PAT-NO: 6070284

DOCUMENT-IDENTIFIER: US 6070284 A

TITLE: Wafer cleaning method and system

DATE-ISSUED: June 6, 2000

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Garcia; Alejandro	Union City	CA		
Krick; Brent	Mountain View	CA		
Nichtawitz; Anthony	Lima			PE
Nordeen; Daniel	Boulder Creek	CA		
Oen; Josh	Fremont	CA		
Smith; Kenneth	Cupertino	CA		
Suro; Vincent	Sunnyvale	CA		
Wolf; Daniel	San Jose	CA		

US-CL-CURRENT: 15/102; 15/77, 15/88.3

ABSTRACT:

A wafer cleaning apparatus provides two opposed brushes for brushing a vertically disposed wafer in a tank which can contain a process liquid. A pressure controller adaptively controls the pressure exerted by the brushes on the wafer to compensate for brush wear. Rim driving wheels engage the wafer periphery with a porous jacket coupled to a fluid delivery system, thereby simultaneously rotating and cleaning the periphery of the wafer. The apparatus includes a fluid delivery system for separately and independently delivering a plurality of constituents of a cleaning solution to the brushes, thereby ensuring that a freshly mixed cleaning solution reaches the wafer. The tank can be filled with a process liquid through which megasonic waves provided by a transducer can propagate and impinge upon the wafer thereby enhancing the cleaning of the wafer or the brushes.

33 Claims, 10 Drawing figures

Exemplary Claim Number: 33

Number of Drawing Sheets: 9

Full	Title	Citation	Front	Review	Classification	Date	Reference	Claims	RMAC	Drawn De
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☐ 12. Document ID: US 5974680 A

L5: Entry 12 of 18

File: USPT

Nov 2, 1999

US-PAT-NO: 5974680

DOCUMENT-IDENTIFIER: US 5974680 A

**** See image for Certificate of Correction ****TITLE: Apparatus for use in cleaning wafers

DATE-ISSUED: November 2, 1999

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Anderson; Gary L.	St. Ann	MO		
Wilson; Keith	El Cerrito	CA		

US-CL-CURRENT: 34/58; 134/902

ABSTRACT:

A semiconductor wafer scrubbing and drying apparatus is capable processing wafers in a vertical orientation from start to finish. The apparatus moves the wafers in a generally vertical direction from an entry station of the apparatus to a dryer of the apparatus. The wafers enter the apparatus in a cassette and exit in another cassette in the same order as they were in the entry cassette to preserve individual wafer identity. The apparatus is constructed so that the compartment in which the wafers are handled is isolated and the components handling the wafers in that compartment are made of a fluorinated plastic. The actuators driving the motion of the wafer handling components are located in another compartment. A rinsing device in the wafer handling compartment is activated and deactivate for rinsing one of the wafers without the use of valves in the rinse line.

24 Claims, 19 Drawing figures

Exemplary Claim Number: 1

Number of Drawing Sheets: 18

Full	Title	Citation	Front	Review	Classification	Date	Reference				Claims	KWAC	Drawn Up
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☐ 13. Document ID: US 5927085 A

L5: Entry 13 of 18

File: USPT

Jul 27, 1999

US-PAT-NO: 5927085

DOCUMENT-IDENTIFIER: US 5927085 A

TITLE: Commercially viable counter-top beverage dispenser with passive thermal insulation

DATE-ISSUED: July 27, 1999

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Waldman; Joseph	Bayport	NY	11705	

US-CL-CURRENT: 62/129; 215/395, 220/23.89, 220/592.17, 62/457.4

ABSTRACT:

A beverage carton dispenser for self-service coffee distribution is provided with passive thermal insulation, a locking means to prevent undesirable beverage-carton slip-out during times when a user employs a steep pouring angle. A vent aperture is provided to relieve inner-air pressure when a milk carton is being installed or removed. A pour handle and re-useable refrigerant gel are also provided. The device is simple, inexpensive and solves the problem of providing a commercially viable counter-top milk dispenser which keeps milk cold in a room-temperature environment without the use of open ice with dripping and puddling water and without active refrigeration requiring an energy input. The presence of the pour handle makes dispensing the beverage easier, safer, and more convenient and provides the user with greater control over pouring the beverage from the container.

23 Claims, 8 Drawing figures

Exemplary Claim Number: 1

Number of Drawing Sheets: 4

Full	Title	Citation	Front	Review	Classification	Date	Reference			Claims	KWC	Draw. De

☐ 14. Document ID: US 5902402 A

L5: Entry 14 of 18

File: USPT

May 11, 1999

US-PAT-NO: 5902402

DOCUMENT-IDENTIFIER: US 5902402 A

TITLE: Device for chemical wet treatment

DATE-ISSUED: May 11, 1999

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Durst; Johann	Pliezhausen			DE
Sigel; Holger	Pliezhausen			DE
Schulz; Werner	Aalen			DE

US-CL-CURRENT: 118/423; 118/428, 118/429, 118/501, 118/58, 118/602, 118/61, 118/63, 118/64, 118/DIG.2, 134/61, 134/902, 414/937, 414/940, 414/941, 427/430.1

ABSTRACT:

A device for chemical wet treatment of substrates has a tank containing a treatment fluid for treating the substrates. At least one substrate carrier for supporting the substrates within the tank is provided. At least one substrate lifting device for lifting the substrates off the substrate carrier is provided. A lifting apparatus for lifting and lowering the substrate carrier is positioned in the tank.

The lifting apparatus has a first transport carriage connected to the substrate lifting device and a second transport carriage connected to a holder of the substrate carrier. The first and second transport carriages are connected to one another by a jointed connection.

19 Claims, 16 Drawing figures
Exemplary Claim Number: 1
Number of Drawing Sheets: 12

Full	Title	Citation	Front	Review	Classification	Date	Reference	Claims	KNIC	Drawing
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☐ 15. Document ID: US 5868865 A

L5: Entry 15 of 18

File: USPT

Feb 9, 1999

US-PAT-NO: 5868865
DOCUMENT-IDENTIFIER: US 5868865 A

TITLE: Apparatus and method for washing treatment

DATE-ISSUED: February 9, 1999

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Akimoto; Masami	Kumamoto			JP

US-CL-CURRENT: 134/33; 134/3, 134/32, 134/61

ABSTRACT:

Disclosed is an apparatus for washing treatment which comprises a washing solution supply source filled with a washing solution required for chemical washing of a wafer, a spin chuck for rotatably holding a wafer to be treated, a nozzle communicating with the washing solution supply source, for supplying a washing solution from the washing solution supply source onto the wafer held on the spin chuck, temperature controlling device for controlling the temperature of the washing solution to be supplied to the wafer from the nozzle, and a temperature controlled cover closely provided so as to cover the wafer held on the spin chuck, for preventing a substantial temperature variation of the washing solution present on the wafer.

17 Claims, 17 Drawing figures
Exemplary Claim Number: 1
Number of Drawing Sheets: 9

Full	Title	Citation	Front	Review	Classification	Date	Reference	Claims	KNIC	Drawing
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☐ 16. Document ID: US 5679055 A

L5: Entry 16 of 18

File: USPT

Oct 21, 1997

US-PAT-NO: 5679055

DOCUMENT-IDENTIFIER: US 5679055 A

TITLE: Automated wafer lapping system

DATE-ISSUED: October 21, 1997

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Greene; George W.	Burlington	MA		
Albrecht; Peter D.	Spartanburg	SC		
Strittmatter; Kenneth D.	Mauldin	SC		
Hidalgo; Rafael	Greenville	SC		

US-CL-CURRENT: 451/10; 451/285, 451/286, 451/287, 451/288, 451/289, 451/41

ABSTRACT:

An automated wafer lapping system including a robot which loads wafers from a cassette into a wafer carrier on a lapping machine one at a time and one after another. The robot is capable of delivering lapped wafers to a thickness gauging device for measuring the wafer thickness and recalibrating the lapping machine between each run. Openings in the wafer carriers for receiving wafers are sized closely to the wafer for minimal relative motion between the wafer and carrier. A centering jig and search program for the robot facilitate fast location of the wafers in the openings. The lapping system also inspects wafers for defects and sorts them accordingly after lapping.

36 Claims, 18 Drawing figures

Exemplary Claim Number: 36

Number of Drawing Sheets: 12

Full	Title	Citation	Front	Review	Classification	Date	Reference			Claims	KMC	Draw. De
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17. Document ID: US 5655954 A

L5: Entry 17 of 18

File: USPT

Aug 12, 1997

US-PAT-NO: 5655954

DOCUMENT-IDENTIFIER: US 5655954 A

TITLE: Polishing apparatus

DATE-ISSUED: August 12, 1997

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Oishi; Toshio	Numazu			JP
Shin; Shoichi	Tagata-gun			JP
Tsunada; Masafumi	Numazu			JP
Ishida; Masahiro	Yokohama			JP

Mase; Yasukazu

Yokohama

JP

US-CL-CURRENT: 451/67; 134/62, 451/287, 451/288, 451/289, 451/66

ABSTRACT:

Provided is a polishing apparatus which comprises a polishing mechanism for polishing a wafer taken out from a cassette, an attaching-detaching device for attaching to and detaching the wafer from the polishing mechanism, a device for cleaning the polished wafer, and a transportation device for transporting the wafer between the cassette, polishing mechanism, attaching-detaching device, and cleaning device. These devices are arranged individually in compartments. A working chamber is divided into a plurality of compartments by means of partitioning devices. A device for polishing a workpiece is set in one of the compartments. The apparatus is also provided with communication devices for internally connecting the adjacent compartments which are divided by the partitioning devices. The apparatus may further comprise devices for individually controlling the respective internal pressures of the compartments or a device for generating an air flow in the form of a laminar flow in each of the compartments.

21 Claims, 8 Drawing figures

Exemplary Claim Number: 1

Number of Drawing Sheets: 8

Full	Title	Citation	Front	Review	Classification	Date	Reference		Claims	NAME	Drawn By
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18. Document ID: US 5437733 A

L5: Entry 18 of 18

File: USPT

Aug 1, 1995

US-PAT-NO: 5437733

DOCUMENT-IDENTIFIER: US 5437733 A

TITLE: Method and apparatus for treating a substrate

DATE-ISSUED: August 1, 1995

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Okumura; Katsuya	Yokohama			JP

US-CL-CURRENT: 134/34; 134/117, 134/122R, 134/2, 134/48, 204/194, 205/148, 205/157, 205/172, 205/88, 205/96, 216/23, 216/99, 430/434, 438/747

ABSTRACT:

A plane of a treatment liquid holder having a number of through holes faces a treatment surface of a substrate. A treatment liquid is held between the treatment surface and the liquid holder by utilizing a surface tension of the treatment liquid. Since the treatment liquid is applied only to the treatment surface, an extremely small amount of treatment liquid suffices for the treatment. In addition, since a fresh treatment liquid can be used in every treatment, cross-contamination is suppressed and the treatment can be performed with safety at a low cost.

31 Claims, 20 Drawing figures

Exemplary Claim Number: 1,14

Number of Drawing Sheets: 7

Full	Title	Citation	Front	Review	Classification	Date	Reference	Claims	FIGS	Drawing
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